

PATENT AND TRADEMARK OFFICE
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT
(Use several sheets if necessary)Att'y Docket: AKUCHI P1630SP2
Examiner: John Hoffmann
Group: 1731
Applicant: Akira IKUSHIMA, Kazuya SAITO, Takashi MIURA and Shogo NASUDA

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Sub-Class	Filing Date, If Appropriate
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	4,157,253	Jun. 1979	Hemquist		
	4,182,664	Jan. 1980	Maklad		
	5,267,343	Nov. 1993	Lyons		
	5,620,496	Apr. 1997	Erdogan		
	5,983,673	Nov. 1999	Urano		
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FOREIGN PATENT DOCUMENTS

Examiner Initials	Document Number	Date	Country	Sub-Class	Class	Translation Yes No
	0 687 924 A1	Dec. 20, 1995	EPO			
	2808457	Aug. 1974	Germany			
	4-342427	Nov. 1992	Japan			(To follow)
	4-342436	Nov. 1992	Japan			(To follow)
	6-199539	Jun. 7, 1994	Japan			
	52-94657	Nov. 1993	Japan			
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"Thermal Annealing of Defects Induced by ArF Excimer Laser Irradiation in a SiO₂", Japanese Society of Applied Physics, Catalog No. AP 90110-02 (English Translation) (To follow)

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ROTHSCHILD, Mordechai, Daniel J. EHRLICH and David C. SHAVER, "Eximer Laser Induced Damage in Fused Silica", *Microelectronic Engineering* 11, 1990, pp. 167-172.

"Temperature Dependence of the E' Center Creation in Silica Glasses", *Physica Status Solidi (b)*, vol. 147, No. 1, 1988, pp. k1-k4.

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Date Considered

10/2-19-04